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TRANSMITTAL MESSAGE/COVER SHEET

Date: January 21, 2000

PLEASE DELIVER THE FOLLOWING PAGES TO:

Name: Examiner G. Cantelmo
Company/Firm: U.S. Patent and Trademark Office
Fax No.: 703-305-6078
Pages: (including this sheet) - 11
Re: U.S. Patent Appln. No. 08/902,331
Filed: July 29, 1997 - Title: Magnetron Atomization Source
And Method of Use
Our Ref.: 622/42052DV
From: James F. McKeown
Firm: Evenson, McKeown, Edwards & Lenahan, P.L.L.C.
Fax No.: (202) 628-8844

MESSAGE: Attached is a proposed After-Final Response. Please advise if you have any objections or changes. Jim McKeown

THIS MESSAGE IS INTENDED FOR THE USE OF THE INDIVIDUAL OR ENTITY TO WHICH IT IS ADDRESSED AND MAY CONTAIN INFORMATION THAT IT IS PRIVILEGED, CONFIDENTIAL AND EXEMPT FROM DISCLOSURE UNDER APPLICABLE LAW. IF THE READER OF THIS MESSAGE IS NOT THE INTENDED RECIPIENT OR THE EMPLOYER OR AGENT RESPONSIBLE FOR DELIVERING THE MESSAGE TO THE INTENDED RECIPIENT, YOU ARE HEREBY NOTIFIED THAT ANY DISSEMINATION, DISTRIBUTION, OR COPYING OF THIS COMMUNICATION IS STRICTLY PROHIBITED. IF YOU HAVE RECEIVED THIS COMMUNICATION IN ERROR, PLEASE NOTIFY US IMMEDIATELY BY TELEPHONE (COLLECT), AND RETURN THE ORIGINAL MESSAGE TO US AT THE ABOVE ADDRESS VIA U.S. POSTAL SERVICE. THANK YOU.

DRAFTAttorney Docket: 622/42052DV
PATENTIN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: PIUS GRUENENFELDER ET AL.

Serial No.: 08/902,331 Group Art Unit: 1753

Filed: JULY 29, 1997 Examiner: Cantelmo, G.

Title: MAGNETRON ATOMIZATION SOURCE
AND METHOD OF USE**AFTER-FINAL RESPONSE**
EXPEDITED HANDLING REQUESTEDVIA FACSIMILE - 703-305-6078Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

The following is responsive to the Office Action mailed
April 9, 1999.

IN THE SPECIFICATION

Page 10, between lines 14 and 15 insert the following
paragraph.

--The above-described relationship between d_{11} , (the maximal distance of the new atomization surface to the disk surface to be coated) and r_{13} (the radius of the circular workpiece disk) allow a target taper to be defined by the difference between D_{112} and the distance a_1 which represents the distance spanned by an interior surface F_q , i.e. $co=d_{13}-a_1$. The disclosed relationship and the upper and lower values of d_0 can thus be represented by the following:

$$0.2\phi_{13} \leq d_{113} \leq 0.5\phi_{13}$$

(1)